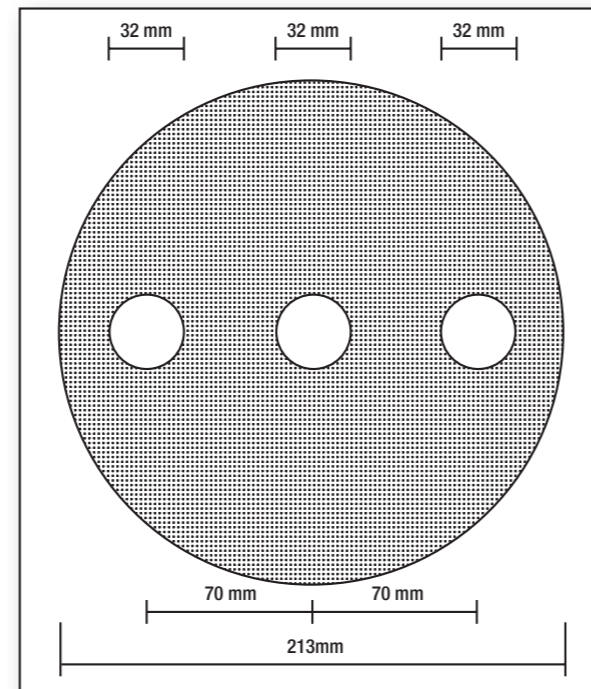


Evatec offers a wide range of Balzers BAK coaters from 0.5 - 1.4m. The PDS is available for both new and retrofit installations.

Installation Requirements	
Source size	213mm ϕ
Electrical Power	16kVA @400V AC
Water	14l/min @ 18-20°C
Gas	Ar & 2nd process gas



Installation requires only three accessible standard feedthroughs in the chamber

PDS

Plasma source
for precision optics



About Evatec

Evatec offers complete solutions for thin film deposition and etch in the optical and semiconductor markets. Evatec engineers are able to offer practical production advice from R&D to prototyping and mass production. We recognize that no single technique offers the answer to all problems. With a technology portfolio including standard and enhanced evaporation as well as sputter, we are ready to offer sampling services and custom engineering to meet our customers' individual needs.

We provide sales and service through our global network of local offices. For more information visit us at www.evatecnet.com or contact our head office.

Evatec Ltd.

Lochrietstrasse 14
CH-8890 Flums
Switzerland
Tel: + 41 81 720 1080
Fax: + 41 81 720 1081
info@evatecnet.com
www.evatecnet.com

Kick start

your evaporation process...

...with the PDS plasma solution

Benefits of PIAD processes

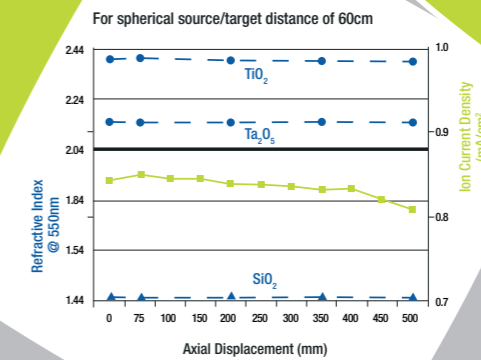
- Higher film densities
- Lower temperature processing
- Improved optical properties

5. BAK 1401

Source suitable for up to 1.5m diameter calottes

4. Refractive Index Profile

Excellent index uniformity

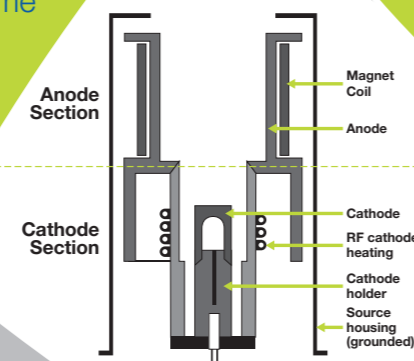


3. PDS in the flesh

"Top ring gas injector" for process gas enables stoichiometry even at high rates

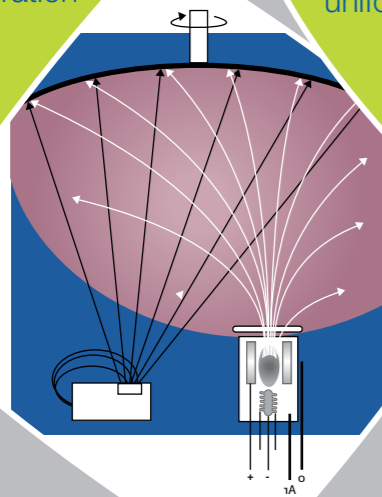
2. Superior design of PDS

RF inductive heating of cathode for best uniformity and lifetime



1. Deposition layout

PIAD configuration



With its inherent flexibility to handle many different substrate geometries and processes, evaporation remains the industry standard for precision optical processes. In Plasma Ion Assisted Deposition (PIAD), the addition of a plasma source to the coating chamber provides a highly energetic plasma into the evaporation plume of electron beam guns or thermal evaporators. The plasma increases the momentum of deposited atoms both prior to condensation and during the formation of the film on the substrate producing films with improved density, mechanical and optical properties.

Just three of the reasons to choose PDS

High throughput

The PDS enables high deposition rates for reactive processes over large calotte sizes up to 1.5m diameter. The source is ideal for high throughput production in applications like imaging and colour separation with demanding optical specifications.

Easy to retrofit

Simple control integration into Evatec's Khan make the PDS the perfect choice for new or retrofit installations.

Low running and maintenance costs

Maintenance is restricted to simple cleaning of the anode liner and other small parts plus periodic replacement of the cathode.